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AMENDMENTS TO THE CLAIMS

Please amend Claims 11 and 21 as follows:

1. (original) A lithographic method, comprising:
aligning a patterned mold with respect to an alignment mark disposed on a substrate based upon interaction of a scanning probe with the alignment mark.
2. (original) The method of claim 1, wherein the patterned mold is aligned based upon detection of a tunneling current between the scanning probe and the alignment mark.
3. (original) The method of claim 1, wherein the patterned mold is aligned based upon detection of an interaction force generated between the scanning probe and the alignment mark.
4. (original) The method of claim 1, further comprising moving a probe near the alignment mark.
5. (original) The method of claim 4, wherein the probe is moved near the alignment mark by optical alignment.
6. (original) The method of claim 4, further comprising applying a voltage between the probe and the alignment mark to induce a tunneling current between the probe and the alignment mark.
7. (original) The method of claim 4, wherein the probe has a fixed spatial position relative to the patterned mold.
8. (original) The method of claim 4, wherein the probe is carried on the patterned mold.

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9. (original) The method of claim 1, further comprising urging the aligned mold into a film disposed on the substrate to transfer a relief pattern to the film.

10. (original) The method of claim 7, further comprising exposing thinned regions of the transferred relief pattern.

11. (currently amended) A device formed by a ~~the~~ lithographic method, ~~comprising aligning a patterned mold with respect to an alignment mark disposed on a substrate based upon detection of a tunneling current through the alignment mark of claim 1.~~

12. (original) A lithographic system, comprising:
a controller configured to align a patterned mold with respect to an alignment mark disposed on a substrate based upon interaction of a scanning probe with the alignment mark.

13. (original) The system of claim 12, further comprising a scanning probe alignment system configured to transmit to the controller position reference signals based upon detection of a tunneling current between the scanning probe and the alignment mark.

14. (original) The system of claim 12, further comprising a scanning probe alignment system configured to transmit to the controller position reference signals based upon detection of an interaction force generated between the scanning probe and the alignment mark.

15. (original) The system of claim 12, further comprising a scanning system configured to move the scanning probe near the alignment mark.

16. (original) The system of claim 15, further comprising an optical alignment system configured to cause the scanning system to position the probe near the alignment mark.

17. (original) The system of claim 15, wherein the scanning system is configured to retract the scanning probe to enable the patterned mold to be urged into a film disposed on the substrate to transfer a relief pattern to the film.

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18. (original) The system of claim 12, wherein the controller is configured to cause the scanning system to urge the patterned mold into a film disposed on the substrate to transfer a relief pattern to the film.

19. (original) The system of claim 12, wherein the controller is configured to align the patterned mold in two or more different co-planar directions.

20. (original) A lithographic system, comprising:

a mold having a patterned surface exposed for contact with and configured to be urged into a film disposed on a substrate to transfer a relief pattern to the film; and

a probe configured to interact with a nearby alignment mark disposed on the substrate.

21. (currently amended) The system of claim ~~19~~ 20, wherein the probe is carried on the mold.